



Advances in Thin Films and Nanotechnology

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Message from the Guest Editors

Thin films have shown the potential uses for many important applications, such as energy, environment, architecture, biology, flexible electronics, and so on, due to their low cost, simple preparation, and various controllable properties. This Special Issue aims to highlight recent progress in the exploration of nanomaterial-based thin films for various applications. Issues related to different nanotechnologies in the design, structure, property, and fabrication of thin films are also included.

This Special Issue on “**Advances in Thin Films and Nanotechnology**” intends to present novel examples of nanomaterials, structural design and optimization, properties, and preparations for all thin films. Topics include, but are not limited to:

- The structure and properties of thin films;
- Nanomaterial-based functional thin films;
- Film design;
- Fabrication of thin films employing nanotechnologies;
- Applications of thin films for energy, environment, architecture, biology, flexible electronics, and so on.





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Message from the Editor-in-Chief

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